

SUPPORT FOR THE AMENDMENTS

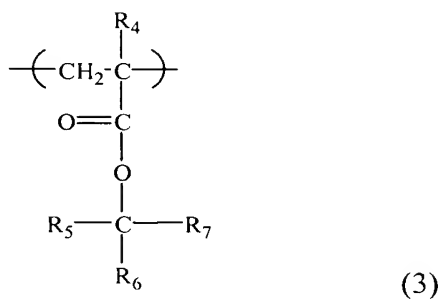
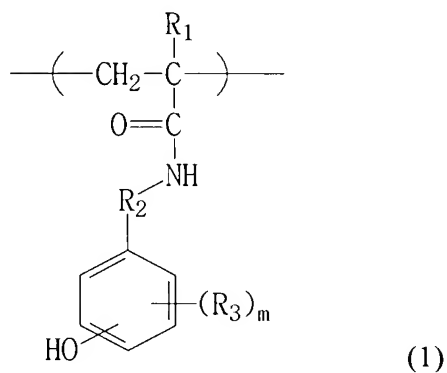
Newly-added Claims 23-32 are supported by the specification and the original claims. Accordingly, no new matter is believed to have been added to the present application by the amendments submitted above.

REMARKS

Claims 23-32 are pending. Favorable reconsideration is respectfully requested.

The present invention relates to a positive radiation-sensitive resin composition, comprising:

(A) a polymer containing structural units represented by formula (1), formula (3), and structural units obtained from p-isopropenylphenol,



where

R₁ is a hydrogen atom or a methyl group,

R₂ is $\text{---}(\text{CH}_2)_n\text{---}$,

n is an integer of 0 to 3, R₃ is an alkyl group of 1 to 4 carbon atoms,

m is an integer of 0 to 4,

R₄ is a hydrogen atom or a methyl group,

R₅ to R₇ are each an alkyl group of 1 to 4 carbon atoms, an alicyclic hydrocarbon group of 4 to 20 carbon atoms, an aromatic group or a substituted hydrocarbon group, wherein at least one hydrogen atom in any one of these hydrocarbon groups is replaced with a polar group other than a hydrocarbon group, wherein R₅ to R₇ may be the same or different, and when any two of R₅ to R₇ are alkyl groups or substituted alkyl groups, their alkyl chains may be bonded to each other to form an alicyclic hydrocarbon group of 4 to 20 carbon atoms or a substituted alicyclic hydrocarbon group;

(B) a component which generates an acid by irradiation with radiation; and

(C) an organic solvent.

The rejection of the claims under 35 U.S.C. §102(b) over Hiroyuki is respectfully traversed. The reference fails to disclose the claimed composition.

Claim 23 requires that polymer A contains structural units represented by formula (1). Hiroyuki fails to disclose a polymer containing structural units represented by formula (1). Accordingly, the reference fails to disclose the claimed composition. Therefore, withdrawal of this ground of rejection is respectfully requested.

The rejections of the claims under 35 U.S.C. §103(a) over Aoai et al. alone and in view of Ohta et al., Jeon et al. and Ohta et al. are respectfully traversed. These references fail to suggest the claimed composition.

The polymer A specified in Claim 23 contains p-isopropenylphenol units. The presence of that unit in a resist film having a large thickness (80 μm or more) provides a higher sensitivity as compared to a film that does not contain p-isopropenylphenol units. This striking effect is clearly shown by Comparison Examples 12-15, which do not contain p-isopropenylphenol units and the other Examples which contain p-isopropenylphenol units.

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Aoai et al. alone or in combination with Ohta et al., Jeon et al. or Ohta et al. fail to suggest this striking result.

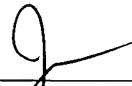
In view of the foregoing, the claimed composition is not obvious over Aoai et al. alone and in view of Ohta et al., Jeon et al. or Ohta et al. Accordingly, withdrawal of these grounds of rejection is respectfully requested.

The obviousness-type double patenting rejections are believed to be moot in view of the Terminal Disclaimer submitted herewith.

Applicants submit that the present application is in condition for allowance. Early notice to this effect is earnestly solicited.

Respectfully submitted,

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